

INFORMATION DISCLOSURE CITATION

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FIS920030330US1

SERIAL NO.
10/10/2009 693199

Huang et al.

FILING
10/24/03

GROUP
1752

U.S. PATENT DOCUMENTS

*EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
ACW	2002/0081520	06-27-02	Sooriyakumaran et al.			
	2001/0036594	11-01-01	Kozawa et al.			
	6,531,260	03-11-03	Iwasawa et al.			
	6,420,088	07-16-02	Angelopoulos et al.			
	6,623,909	09-23-03	Hatakeyama et al.			
	2003/0113658	06-19-03	Ebata et al.			
	6,043,003	03-28-00	Bucchignano et al.			
	6,037,097	03-14-00	Bucchignano et al.			
	5,712,078	01-27-98	Huang et al.			
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ACW	2002/0090572	07-11-02	Sooriyakumaran et al.			

FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
							YES	NO

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

ACW	"Effects of resist components on image spreading during postexposure bake of chemically amplified resists", Hinsberg et al. Proceedings of SPIE Vol. 3999 (2000), ppgs. 148-160
	"Determination of coupled acid catalysis-diffusion processes in a positive-tone chemically amplified photoresist" Houle et al. Journal Vac. Sci. Technology B 18 (4) Jul/Aug 2000, ppgs. 1874-1885
	"Direct measurement of the reaction front in chemically amplified photoresists" Lin et al. Science, Vol. 297, 19 July 2002, ppgs. 372-375
ACW	"Modeling and simulations of a positive chemically amplified photoresist or ex-ray lithography", Krasnoperova et al., Journal Vac. Sci. Technology B 12 (6) Nov/Dec 1994, ppgs. 3900-3904

EXAMINER

Dr. C. Wallace

DATE CONSIDERED

June 10, 2004

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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ACW	5,985,524	11-16-99	Allen et al.			
ACW	2002/0058204	05-16-02	Khojasteh et al.			
ACW	2003/0073040	04-17-03	Iwasawa et al.			
ACW	6,420,084	07-16-02	Angelopoulos et al.			

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						YES	NO
ACW	0 628 876 A1	05-25-94	EPO				

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ACW	Appl. no. 10/241,937, FIS9-2002-0057US1 "Low silicon-outgassing resist for bilayer lithography" Kwong et al. Filed 9-11-02
	Appl. no. 10/604,082, FIS9-2003-0159US1 "Process for forming features of 50 nm or less half-pitch with chemically amplified resist imaging" Medeiros et al., Filed 06-25-03
ACW	Appl. no. 10/026,184, FIS9-2001-0380US1 "Underlayer compositions for multilayer lithographic processes", Khojasteh et al., Filed 12-21-01
	Appl. No. 10/079,289, YOR9-2000-0693US2, "Substantially transparent aqueous base soluble polymer system for use in 157 nm resist applications" Sooriyakumaran et al., Filed 02-20-02

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